

# **Environmentally Acceptable Photoresist Processing For Integrated Circuit Manufacture By Paula M. Wetmore**

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**Brevetto ep0493923a1 - diazo sensitizers of**

This solubility is preserved in the positive photoresist process in which the exposed, environmentally acceptable developer Citazioni di brevetti. Brevetto

**Www.faqs.orgwww.faqs.org**

Inventor's name Country City/State Last publication Number of Patent applications; Agnar Aa: NO: Rissa: 2014-02-13 / 20140042837 - THREE PHASED BALANCED OR UNBALANCED

**Ieee xplore: semiconductor manufacturing, ieee**

were utilized to demonstrate the potential for a new "dry" lithographic process. Photoresist for environmentally benign environmentally acceptable.

**Brevetto us6764552 - supercritical solutions for**

and titled Supercritical Solutions for Cleaning Photoresist and Post generated by the various integrated circuit processing Wetmore; Paula M.

**Immersion lithography with using of**

more environmentally acceptable compounds than Chalcogenide photoresists based on thermal ty is observed in this process only in arsenic

**Patent us6846380 - substrate processing apparatus**

Microscale devices such as integrated circuits processing apparatus 10 is integrated with a processing medium distribution Wetmore; Paula M

**Patent us5268260 - photoresist develop and strip**

cationically cured resists and solder masks and Vacrel photoresists. environmentally acceptable, Adhesion promotion in photoresist lamination and processing:

**Environmentally acceptable photoresist processing**

Title: Environmentally acceptable photoresist processing for integrated circuit manufacture: Authors: Wetmore, Paula M. Affiliation: AA(Phasex Corp., Lawrence, MA.)

**Patent us6156221 - copper etching compositions,**

environmentally acceptable, has high capacity, to have a commoning bar etchant or process that would not require a photoresist application.

**Chemical pre-treatment and biological destruction**

.FIELD OF THE INVENTIONThe invention described herein relates to the destruction of environmentally photoresist, the photolithographic process acceptable

**New chemistries for advanced printed circuit board**

New Chemistries for Advanced Printed Circuit environmentally acceptable manner. These photoresists are also more acceptable from an

**Textbook- integrated guide to educational**

and printed from software supplied with the converter to afford chromatograms of acceptable An Environmentally Significant integrated circuit,

**Patent us6281135 - oxygen free plasma stripping**

and ashing is more environmentally acceptable. The inventive stripping process for removing photoresist and/or post etch residues comprises generating an

**Spie | proceeding | advanced silicon etching using**

non-corrosive environmentally acceptable silicon etching using high-density plasmas", Proc. SPIE 2639, Micromachining and Microfabrication Process

**Brevetto wo1995024674a1 - stable, ionomeric**

STABLE, IONOMERIC PHOTORESIST EMULSION AND PROCESS OF PREPARATION AND USE THEREOF. Aqueous emulsions, while more environmentally acceptable,

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**Patent us20040154641 - substrate processing -**

it is becoming increasingly expensive to dispose of spent chemistries in an environmentally acceptable This patent describes use of a photoresist, and the

**Environmental considerations for applying**

Environmental Considerations for Applying Photostructurable Liquid a technique for processing photoresist has to for an environmentally acceptable

**Plating in the electronics industry - springer**

Society s 9th Symposium on Plating in the Electronics Industry held under environmentally acceptable Film Photoresist Characteristics for

**Patent wo1987005314a1 - photoresist stripper**

A composition, adapted to strip photoresists from substrates after the protective function of the photoresist has been completed, comprises a mixture of (a)

**Patent us6638875 - oxygen free plasma stripping**

Oxygen free plasma stripping process and ashing is more environmentally acceptable. The inventive stripping process for removing photoresist and/or post

### **Presidential green chemistry challenge awards**

that removes photoresist this new technology is more environmentally benign than the process converting wastes to more environmentally acceptable

### **Patente us6562146 - processes for cleaning and**

providing a partially fabricated integrated circuit, Wetmore; Paula M Compositions and methods for drying patterned wafers during manufacture of

### **Patent us7064070 - removal of cmp and post-cmp**

requirements for every step in the manufacture of integrated circuits, and reduce particulate contamination to acceptable Wetmore; Paula M

### **Patente us4201579 - method for removing**

A method for removing photoresist from to provide an environmentally acceptable photoresist removal process of a photoresist stripping process:

### **Patente us6764552 - supercritical solutions for**

the waste products generated by the various integrated circuit processing Wetmore; Paula M. wafers during manufacture of integrated

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### **Government contracts / supercritical fluid**

Government Contracts. Applications; Processing of Energetic Materials with Environmentally Acceptable Photoresist Processing for Integrated Circuit

### **Presidential green chemistry challenge : award**

The Presidential Green Chemistry Challenge Awards Program process is a major source of environmentally harsh environmentally acceptable,

### **United states patent [19] [11] patent number:**

427531 ments and Process Studies Online , applying a photoresist to a Wafer s surface in a particular ing and Which are environmentally acceptable.

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more environmentally acceptable compounds as a base for photoresist process in and films using interference lithography and chalcogenide

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A Decision Support System for Integrated Circuit Package Selection a transaction processing monitor for distributed transaction processing applications maintains

### **Inventors list za-zc - patent application - faqs**

MOISTURE CURABLE COMPOSITIONS AND METHODS FOR THEIR MANUFACTURE

Methods of laser processing photoresist INSULATION MATERIAL FOR INTEGRATED CIRCUITS

**Inventors list aa-ac - patent application - faqs**

environmentally acceptable multifunctional multiple voltage threshold timing analysis for a digital integrated circuit: 6: photoresist processing methods: 4:

**Environmentally acceptable photoresist processing**

Environmentally Acceptable Photoresist Processing for Integrated Circuit Manufacture. Ms. Paula Wetmore. SBIR Phase I: Plasma Deposited, Environmentally

**Patent us6764552 - supercritical solutions for**

and titled Supercritical Solutions for Cleaning Photoresist and Post generated by the various integrated circuit processing Wetmore; Paula M.

**Advances in resist technology and processing xv |**

Proceedings of SPIE Volume 3333 Advances in Paula M. Gallagher-Wetmore Novel negative photoresist based on polar alicyclic polymers for ArF

**The nanostructuring of surfaces and films using**

The nanostructuring of surfaces and films using interference lithography and chalcogenide more environmentally acceptable process on more environmentally

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Quantitative Analysis of Nail Polish Remover Using Nuclear Magnetic Resonance Spectroscopy Revisited Markus M. Hoffmann, Joshua T. Caccamis, Mark P. Heitz, and Kenneth

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